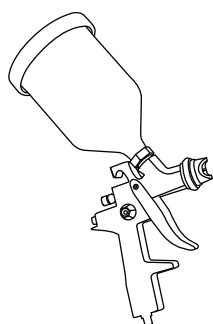


	WAVE 2.0	BASE 2.0	2K
	W 400 WB2 1.3 1.8 bar	W 400 BellAria 1.3 2.0 bar	W 400 BellAria 1.3/1.4 2.0 bar
	W 400 BellAria 1.3 2.0 bar	WS 400 evo base 1.3 HD 2.0 bar	W 400 WBX 1.4 2.0 bar
	WS 400 evo base 1.3 OBS 2.0 bar	LS 400 entech HVLP 1.3 ETS 1.8 bar	WS 400 evo clear 1.4 HD 2.0 bar
	LS 400 entech HVLP 1.3 ETS 1.8 bar	W 400 WBX 1.3 1.8 - 2.0 bar	
	GTi Pro T110 1.3 1.5-2.0 bar	GTi Pro HV25/HV30 1.3 1.5-2.0 bar	GTi Pro TE20/T110/TE10 1.3/1.4 1.5-2.0 bar
	GTi Pro LITE T110 1.3 1.5-2.0 bar	GTi Pro LITE HV25/HV30 1.3 1.5-2.0 bar	GTi Pro LITE TE20/T110/TE10 1.3/1.4 1.5-2.0 bar
	5000 B HVLP 1.2/WSB/1.3 1.6-2.0 bar	5000 B HVLP 1.2/1.3 1.6-2.0 bar	5000 B RP 1.2/1.3/1.4 1.8-2.2 bar
	4000 B HVLP 1.2/WSB/1.3 1.6-2.0 bar	4000 B HVLP 1.2/1.3 1.6-2.0 bar	4000 B RP 1.2/1.3/1.4 1.8-2.2 bar
	5000 B RP 1.2/1.3 2.0 bar	5000 B RP 1.2/1.3 1.6-2.0 bar	5000 B HVLP 1.3/1.4 2.0 bar
	4000 B RP 1.2/1.3 2.0 bar	4000 B RP 1.2/1.3 1.6-2.0 bar	4000 B HVLP 1.3/1.4 2.0 bar
	12.XL-1.3 AQUA/HVLP 1.8-2.0 bar	12.XL-1.3 HVLP/TITANIA 1.8-2.0 bar	13-1.3XL TITANIA/CLEAR 1.8-2.2 bar



BASE 2.0 AND WAVE 2.0 SYSTEMS		
	MATERIAL QUANTITY	PRESSURE
Concealer layer application	100% material opening	See the values in the table below
Drop layer application	70% reduction	25-30% reduction from the values in the table above